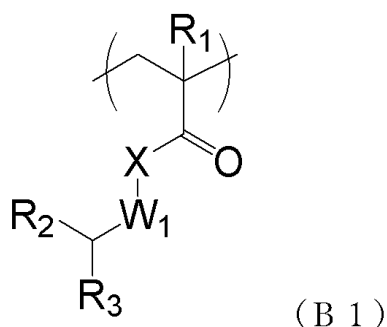


ABSTRACT

TITLE OF INVENTION: COMPOSITION FOR FORMING ORGANIC FILM,
METHOD FOR FORMING ORGANIC FILM, PATTERNING PROCESS, AND
POLYMER

A composition for forming an organic film, containing
(A) material, (B) polymer having a repeating unit
represented by formula (B1), and (C) solvent:



wherein R_1 is a hydrogen atom or a methyl group, R_2 and R_3 are each a monovalent organic group having 10 to 20 carbon atoms and not containing fluorine atom, X is a nitrogen atom or an oxygen atom, and W_1 is a single bond or a divalent linking group having 1 to 10 carbon atoms and not containing fluorine atom and optionally containing an oxygen atom.

A polymer useful for a film forming material, having low environmental impact, and not falling under PFAS. A composition containing the polymer having no coating defects such as pinholes and has excellent coatability, formability and filling characteristic, and method for forming an organic film. A patterning process that uses this composition for forming an organic film.

FIG. 1(A) to 1(F)